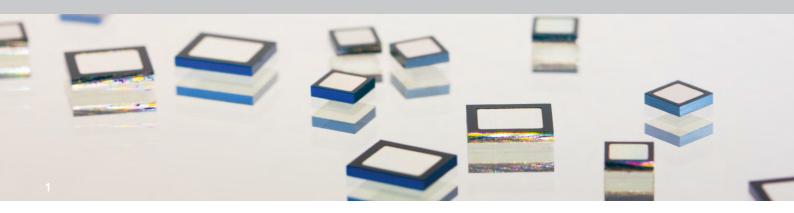


FRAUNHOFER INSTITUTE FOR INTEGRATED SYSTEMS AND DEVICE TECHNOLOGY



1 Silicon chip snubbers for 600 V applications with a polyimide surface passivation (device area of 14.3 mm² and 6.8 mm² respectively)

Fraunhofer Institute for Integrated Systems and Device Technology IISB

Schottkystrasse 10 91058 Erlangen Germany

Contact

Gudrun Weidauer Phone: +49 (0)9131 / 761-176 gudrun.weidauer@iisb.fraunhofer.de

www.iisb.fraunhofer.de

SILICON INTEGRATED RCD-SNUBBER NETWORKS

General description

Based on our established technology for monolithic RC-snubbers the silicon integrated RCD-snubber networks combine a deep trench MOS capacitor with a resistor which is formed by the bulk resistance of the silicon substrate. For the RCD-snubber pn-diodes are integrated into the silicon substrate. Different implementations allow for the realization of RCD-snubbers for voltage rise control and for voltage clamping.

Features

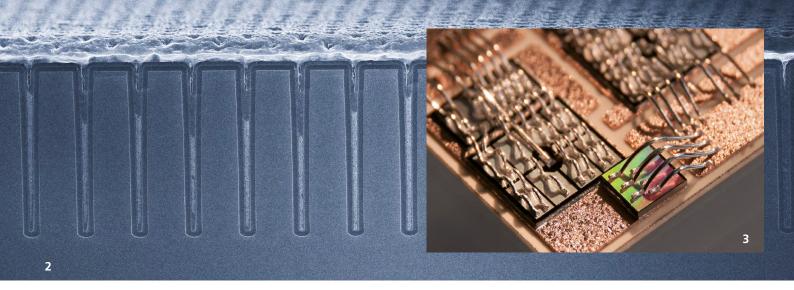
- Available as bare die silicon chips
- Whole back side area can be soldered or sintered onto a power electronic substrate (e.g. DBC, lead frame)
- Very small temperature dependence of the capacitor (< 50 ppm/K)
- Extremely low stray inductance (< 100 pH)

Advantages

- Compact module design (one silicon chip replaces three or more discrete passive components)
- Packaging compatible with power semiconductor devices
- Improved thermal connection to heat sink similar to power semiconductor devices
- Reduced voltage overshoots in power modules
- Improved EMC of power module or power switch

Benefits

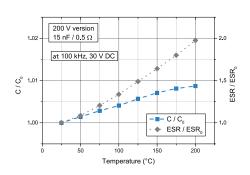
- Cost savings and improved reliability due to uniform packaging
- More competitive products because of technological advantages
- Increased market volume due to conformity with EMC regulations



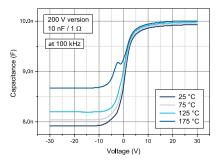
General characteristics

| Nominal voltage | up to 600 V |
|----------------------|-----------------------|
| Temperature range | -40 °C – 200 °C |
| Climatic category | 40 / 200 / 56 |
| Capacitance range | 0.5 nF – 50 nF (typ.) |
| Temp. coefficient of | ~ 50 ppm/K |
| the capacitance | |
| Resistance range | 10 mΩ – 10 Ω (typ.) |
| Temp. coefficient of | ~ 5000 ppm/K |
| the resistance | |
| Blocking voltage of | > 900 V |
| the diode | |

Temperature characteristic of the snubber's capacitor and resistor



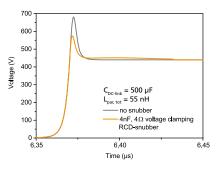
Capacitance voltage characteristics on a lightly doped silicon substrate



In unipolar operation the capacitance is largely independent of the voltage.

Voltage clamping snubber

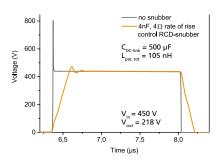
The voltage clamping RCD-snubber limits the voltage overshoot at a protected device (e.g. a MOSFET), as the following graphic illustrates with SPICE simulation results for a half-bridge power module.



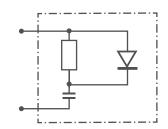
The RCD-snubber for voltage rise control

Voltage rise control snubber

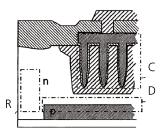
limits the voltage slope during the turn-on and turn-off at a protected device. This is shown below in SPICE simulation results of a half-bridge-based DC/DC converter.



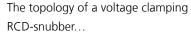
The topology of an RCD-snubber for voltage rise control...

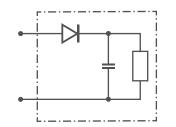


... can also be realized on a silicon chip with a technology that is patented by Fraunhofer IISB (US7738226 B2):

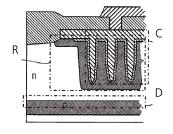


3 Silicon integrated snubber chip assembled on a DBC substrate next to active power electronic devices.





... can be integrated on a silicon chip with a technology that is patented by Fraunhofer IISB (US7738226 B2):



2 Cross-section image of a monolithically integrated capacitor taken by scanning electron microscopy.